# Optical Measurement Systems for Industrial Inspection IV

Part of the SPIE International Symposium

## Optical Metrology

*Munich, Germany, June 13-16, 2005*

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This conference will focus on optical metrology methods and their application for the solution of practical problems in industrial design and production engineering. Relevant applications range from the optical inspection of large scale industrial components to the investigation of microsystems. Special emphasis shall be given to the implementation of new methods and algorithms into complete measurement systems. The application of these systems close-to-production is of general interest. Further on, the integration of modern electro-optical components and inspection strategies for the design of sophisticated systems shall be reported.

- optical metrology
- image processing
- measurement systems
- systems reliability
- active vision/metrology
- remote metrology
- experimental stress analysis
- nondestructive evaluation and fault detection
- shape measurement/reverse engineering
- microstructure measurement
- film thickness measurement
- velocity measurements
- particle measurements and flow analysisi
- vibration analysis
- interferometry
- holographic and speckle techniques
- moire and structured illumination
- photogrammetry
- deflectometry
- fiber optic sensors
- microscopy
- laser ultrasonics
- spectroscopyy

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